

10-17-2000

H52

Filed Via Express Mail

Rec. No.: ELS22395272US

On: OCTOBER 16, 2000

By:

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1634.

Attorney Docket No.:NEKW14.868



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Inventor: KAICHIRO NAKANO, ET AL.

Serial No.: 09/036,219

Filed: March 6, 1998

Title: **CHEMICALLY AMPLIFIED RESIST LARGE IN  
TRANSPARENCY AND SENSITIVITY TO EXPOSURE  
LIGHT LESS THAN 248 NANOMETER WAVELENGTH  
AND PROCESS OF FORMING MASK**

Examiner: J. Chu

Group Art Unit: 1752

October 16, 2000

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Assistant Commissioner for Patents  
**BOX NON-FEE AMENDMENT**  
Washington, D.C. 20231

**RESPONSE TO OFFICE ACTION**

SIR:

In response to the Office Action dated August 9, 2000, the period for responding thereto having been set to expire on November 9, 2000, please consider the following: